

Fig. 4-10 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The constant laser power is 1.5W. The scan speed is 1cm/sec, the grain size of area “a” is about 1.2um

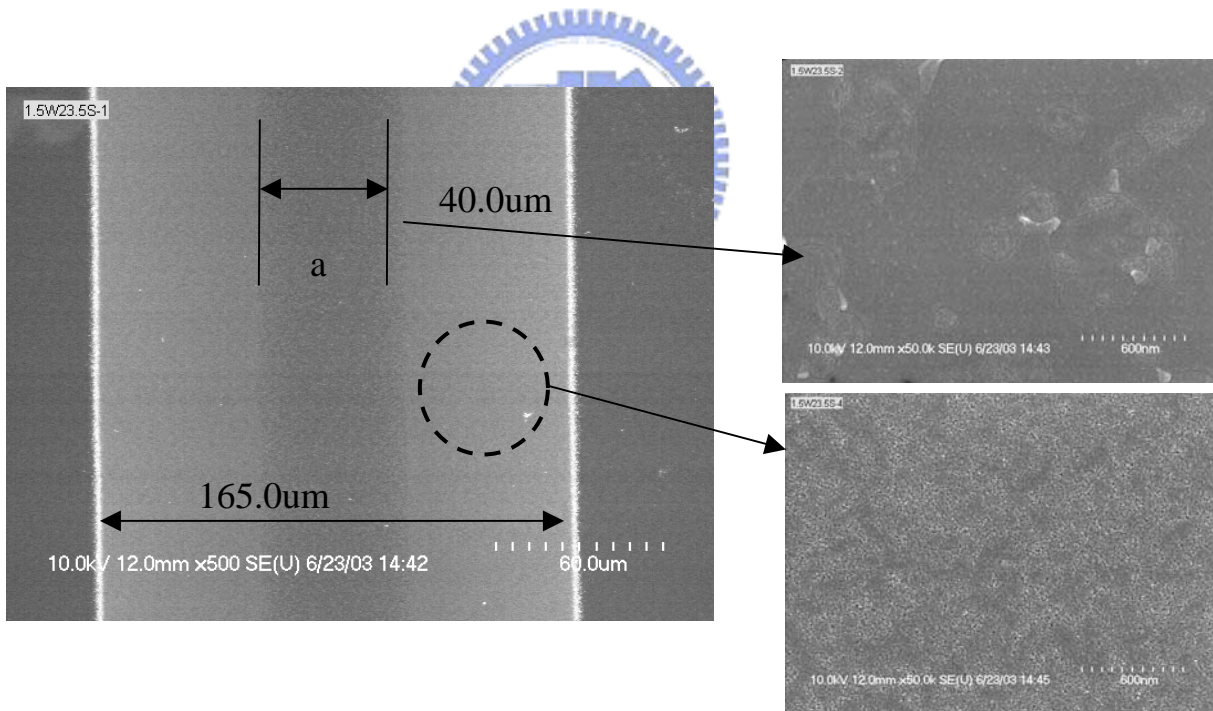


Fig. 4-11 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The constant laser power is 1.5W. The scan speed is 3 cm/sec, the grain size of area “a” is about 0.6um

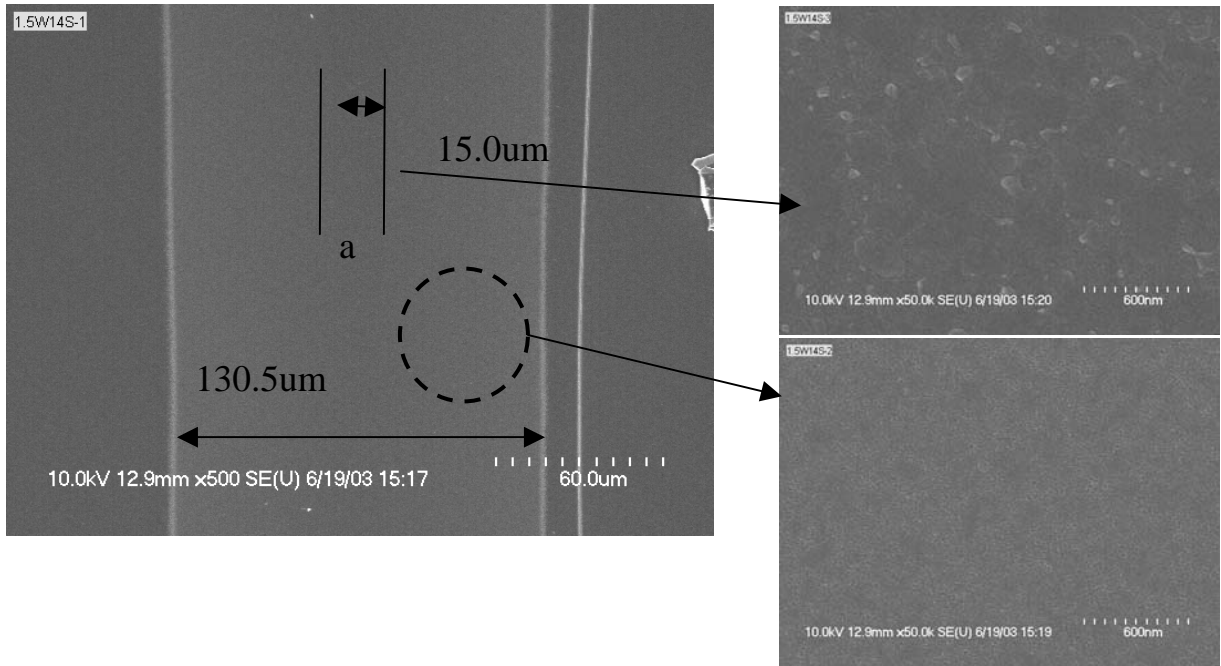


Fig. 4-12 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The constant laser power is 1.5W. The scan speed is 5 cm/sec, the grain size of area “a” is about 0.3um

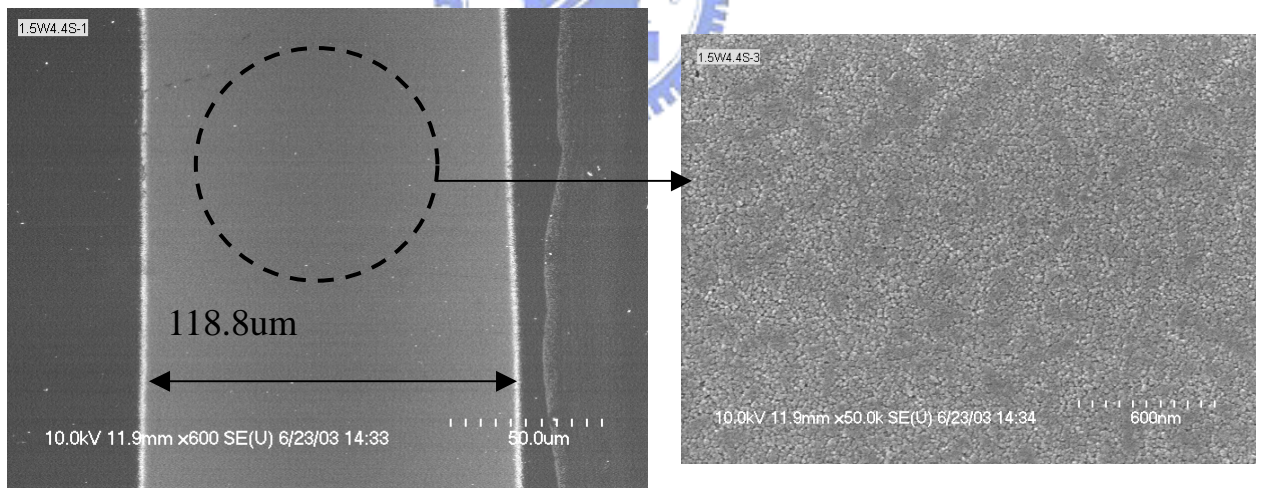


Fig. 4-13 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The constant laser power is 1.5W. The scan speed is 7 cm/sec and center grain size is 0.005um